

forming a molecular film by using a photolytic organic silicon compound that contains an aromatic hydrocarbon group, as a starting material; and

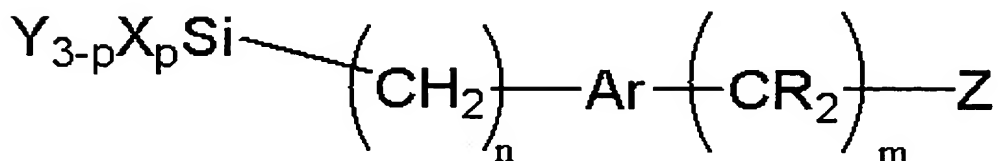
irradiating the molecular film with a light.

2. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n, m, p, Ar, X, Y, and R are as follows:

n is an integer of 0 or more;

m is an integer of 0 or more;

p is an integer of 0 or more;

Ar is an aryl group;

R is a hydrogen atom or a fluorine atom;

X is a halogen group including a chlorine group, an amino group, or an alkoxyl group;

Y is an alkyl group, an aryl group, or a hydrogen atom; and

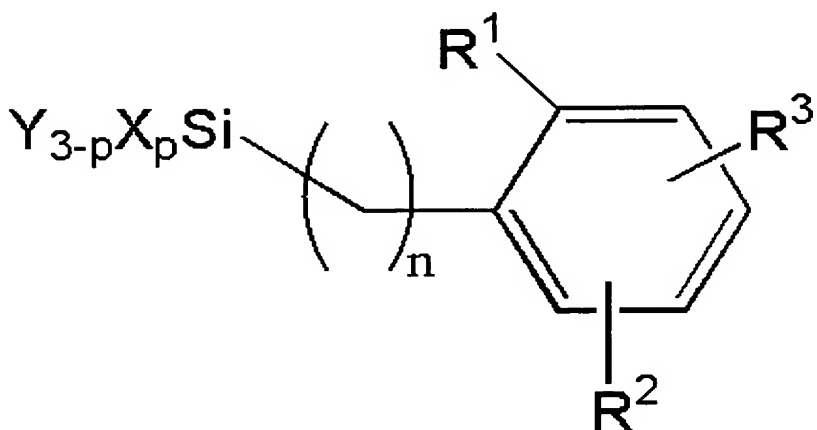
Z is an alkyl group, a perfluoroalkyl group, a silyl group, a cyano group, an amino group, or a thiol group.

3. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n , p , R^1 , R^2 , R^3 , X , and Y are as follows:

n is an integer of 0 or more;

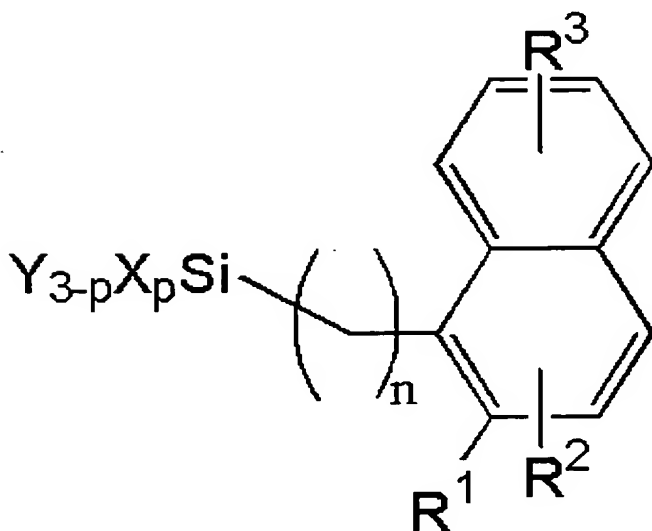
p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

R^2 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

R^3 is a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, an alkyl group containing an organic silicon group, an aryl group, or an alkyl group containing an aryl group;
 X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and
 Y is an alkyl group or an aryl group.

4. (Amended) A method for manufacturing a molecular film pattern, comprising:
- forming a molecular film by using an organic silicon compound as a starting material; and
 - irradiating the molecular film with a light,
- the organic silicon compound having a chemical structure represented by




wherein n , p , R^1 , R^2 , R^3 , X , and Y are as follows:

n is an integer of 0 or more;

p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

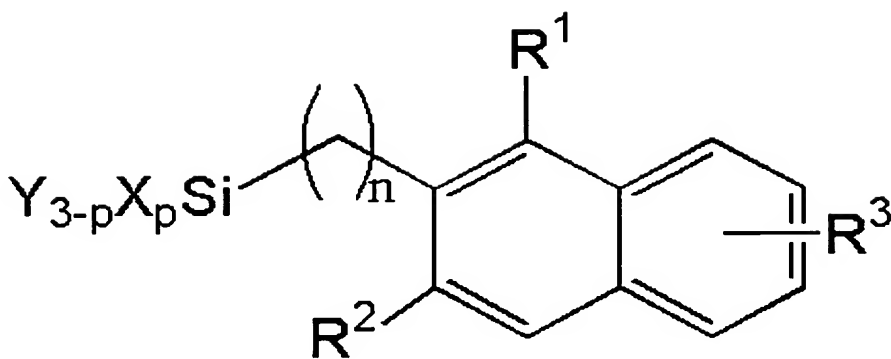
 R^2 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

R^3 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

Y is an alkyl group or an aryl group.

5. (Amended) A method for manufacturing a molecular film pattern, comprising:
- forming a molecular film by using an organic silicon compound as a starting material; and
 - irradiating the molecular film with a light,
 - the organic silicon compound having a chemical structure represented by



wherein n , p , R^1 , R^2 , R^3 , X , and Y are as follows:

n is an integer of 0 or more;

p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

R^2 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

R^3 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

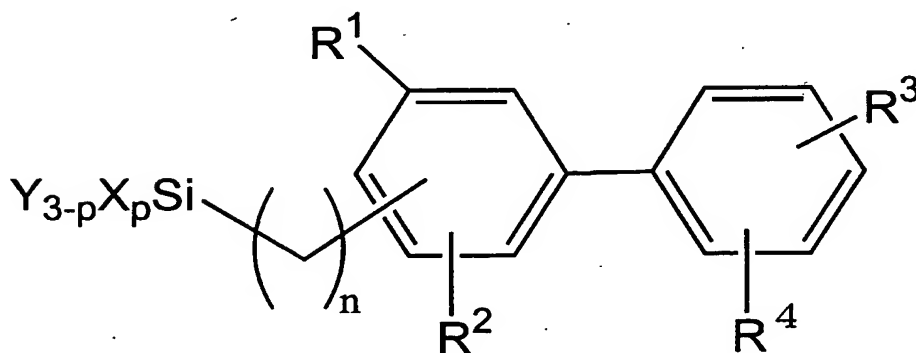
Y is an alkyl group or an aryl group.

6. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n , p , R^1 , R^2 , R^3 , R^4 , X , and Y are as follows:


n is an integer of 0 or more;

p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

R^2 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group,

group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

 R^3 is a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

R^4 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, or an alkyl group containing an organic silicon group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

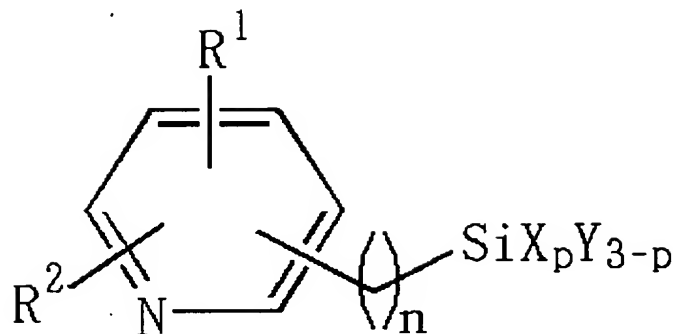
Y is an alkyl group or an aryl group.

7. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n , p , R^1 , R^2 , X , and Y are as follows:

n is an integer of 0 or more;

p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

R^2 is a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, an alkyl group containing an organic silicon group, an aryl group, or an alkyl group containing an aryl group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

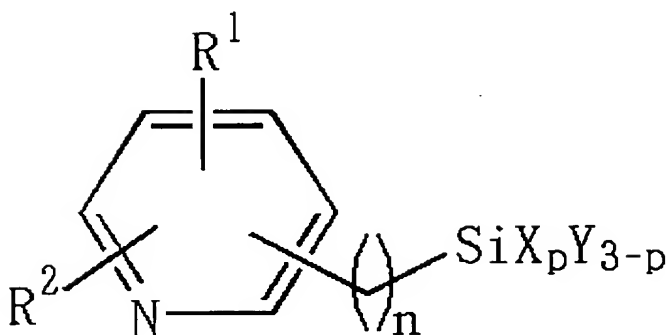
Y is an alkyl group or an aryl group.

8. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n, p, R¹, R², X, Y, and Q are as follows:

n is an integer of 0 or more;

p is an integer of 0 or more;

R¹ is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

R² is a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, an alkyl group containing an alkylamino group, an organic silicon group, an alkyl group containing an organic silicon group, an aryl group, or an alkyl group containing an aryl group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group;

Y is an alkyl group or an aryl group; and

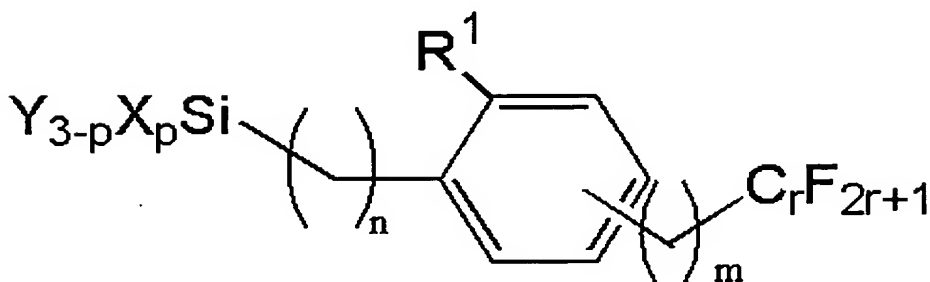
Q is a nitrogen (N) atom, an oxygen (O) atom, or a sulfur (S) atom, each having a hydrogen atom or an alkyl group.

9. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n, m, r, p, R¹, X, and Y are as follows:

n is an integer of 0 or more;

m is an integer of 0 or more;

r is a positive integer;

p is an integer of 0 or more;

R¹ is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

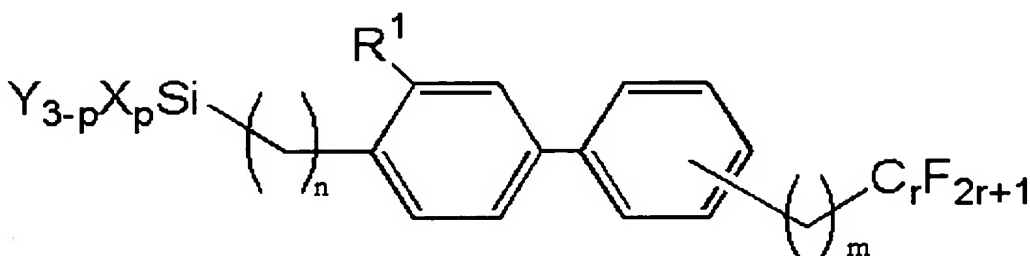
Y is an alkyl group or an aryl group.

10. (Amended) A method for manufacturing a molecular film pattern, comprising:

forming a molecular film by using an organic silicon compound as a starting material; and

irradiating the molecular film with a light,

the organic silicon compound having a chemical structure represented by



wherein n, m, r, p, R¹, X, and Y are as follows:

n is an integer of 0 or more;

m is an integer of 0 or more;

r is a positive integer;

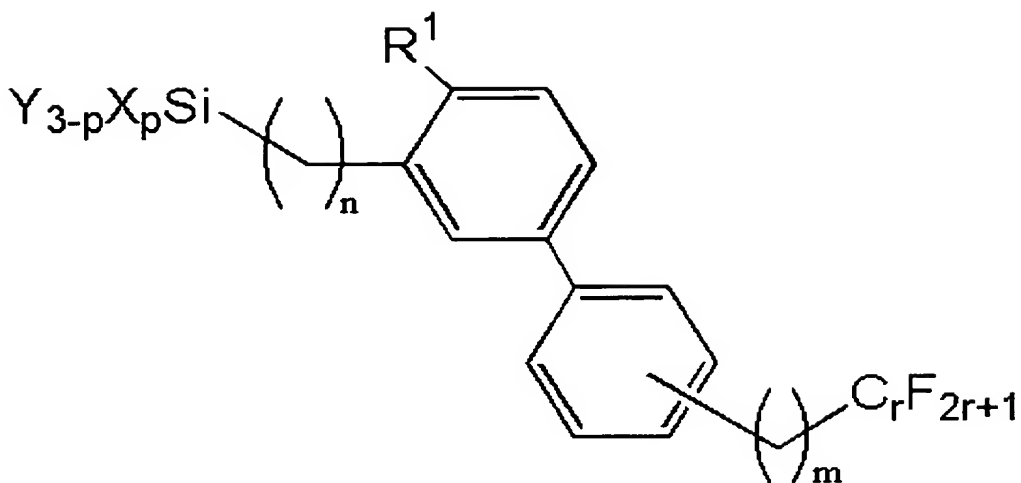
p is an integer of 0 or more;

R¹ is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

Y is an alkyl group or an aryl group.

11. (Amended) A method for manufacturing a molecular film pattern, comprising:
 - forming a molecular film by using an organic silicon compound as a starting material; and
 - irradiating the molecular film with a light,
 the organic silicon compound having a chemical structure represented by



wherein n , m , r , p , R^1 , X , and Y are as follows:

n is an integer of 0 or more;

m is an integer of 0 or more;

r is a positive integer;

p is an integer of 0 or more;

R^1 is a hydrogen atom, a halogen atom, a perfluoroalkyl group, a hydroxyl group, a thiol group, an amino group, an alkylamino group, an alkoxyl group, an alkyl group containing a hydroxyl group, an alkyl group containing a thiol group, an alkyl group containing an amino group, or an alkyl group containing an alkylamino group;

X is a halogen group such as a chlorine group, an amino group, or an alkoxyl group; and

Y is an alkyl group or an aryl group.

12. (Twice Amended) The method for manufacturing a molecular film pattern according to Claim 3, R^1 of the organic silicon compound being a perfluoroalkyl group.

13. (Twice Amended) The method for manufacturing a molecular film pattern according to Claim 3, R^1 of the organic silicon compound being a trifluoromethyl group.

14. (Twice Amended) The method for manufacturing a molecular film pattern according to Claim 1, the thickness of the molecular film being 3 nm or less.

15. (Twice Amended) The molecular film pattern formed by a method for manufacturing a molecular film pattern according to Claim 1.

16. (Twice Amended) A method for manufacturing a semiconductor device further comprising:

forming a molecular film pattern according to the method for manufacturing a molecular film pattern recited in Claim 1.

17. (Amended) A semiconductor device formed by the method for manufacturing a semiconductor device according to Claim 16.

18. (Twice Amended) A method for manufacturing an electro-optical device, comprising:

forming a molecular film pattern according to the method for manufacturing a molecular film pattern recited in Claim 1.

19. (Amended) An electro-optical device formed by the method for manufacturing an electro-optical device according to Claim 18.

20. (Amended) The semiconductor device according to Claim 17,
the semiconductor device comprising an area composed of an organic material.

21. (Amended) The electro-optical device according to Claim 19,
the electro-optical device comprising an organic electroluminescent element.

22. (Twice Amended) A method for manufacturing an electronic device comprising:

a step performed by using the method for manufacturing a molecular film pattern recited in Claim 1.

23. (Twice Amended) An electronic apparatus comprising the electro-optical device according to Claim 19 as a display portion.